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By: *Linda E. Hastings*
LINDA E. HASTINGS
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19/2

Attorney Docket No.:NEKW14.868

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: KAICHIRO NAKANO, ET AL.
Serial No.: 09/036,219
Filed: March 6, 1998
Title: **CHEMICALLY AMPLIFIED RESIST LARGE IN
TRANSPARENCY AND SENSITIVITY TO EXPOSURE
LIGHT LESS THAN 248 NANOMETER WAVELENGTH
AND PROCESS OF FORMING MASK**
Examiner: J. Chu
Group Art Unit: 1752

Assistant Commissioner for Patents
BOX NON-FEE AMENDMENT
Washington, D.C. 20231

October 16, 2000

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RESPONSE TO OFFICE ACTION

S I R :

In response to the Office Action dated August 9, 2000, the period for responding thereto having been set to expire on November 9, 2000, please consider the following: